



NANOCLEAN TOP

Highly alkaline liquid used in ultrasonic process for the removal of cerium oxide, dusts, surfacing residues and fingerprints.

COMPATIBILITY:

- Precision optics: BK7/Quartz/Si/Sapphire
- Non-sensitive organic lense

COMPONENTS:

- Surfactants, strong alkalis

PHYSICO-CHEMICAL DATA:

- pH (1%): 13.1
- Density: 1.505
- Surface tension: 63.6 mN/m

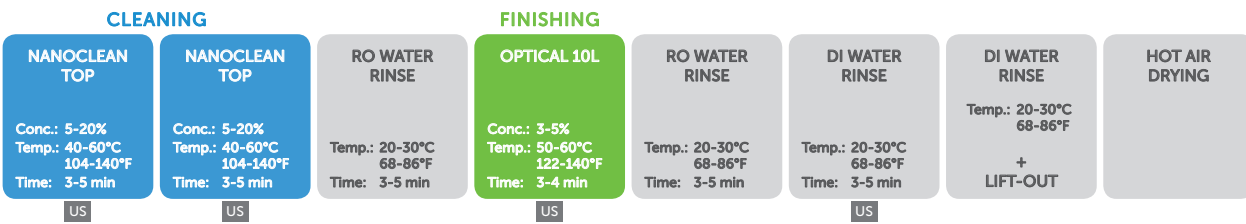
INSTRUCTIONS FOR USE:

The baths must be prepared using demineralised, osmosis or soft water. Optimum use conditions may be affected by the quality of the water used in the baths, as well as the type and quantity of contaminants.

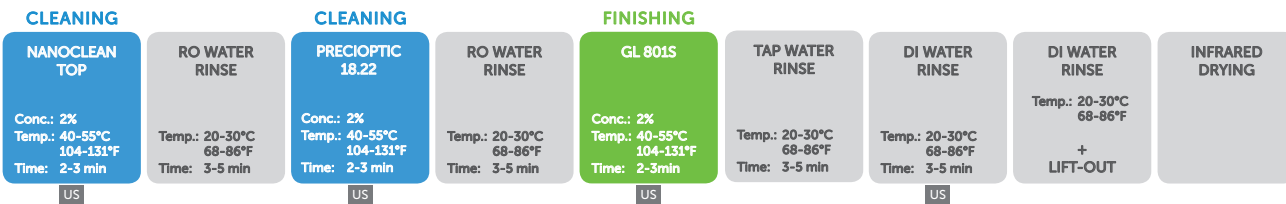
- Concentration: 5 to 20%
- Temperature: 40 to 55°C (104 to 131 °F)
- Time: 3 to 5 minutes

PROCESS EXAMPLES:

- Cleaning molds for CR39



- Cleaning of non-sensitive lenses / removal of surfacing compounds



BENEFITS:

- Effective on a wide range of surfacing residues
- Perfect removal of optical surfacing agents
- Excellent molds cleaner
- Maximum adhesion of hard coating layer and perfect surface preparation prior to A.R. coating
- No harmful components

STORAGE CONDITIONS:

- Keep the recipient hermetically sealed between 5°C and 40°C (41°F and 104°F) in a dry place.
- Always keep in packaging made from the same material as the original packaging.

27/09/19



If you have any questions, please contact our Application Centre on: +41 22 365 46 66

